

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: OHSAWA et al.
Appl. No.: NEW Group: UNASSIGNED
Filed: February 12, 2004 Examiner: UNASSIGNED
For: NOVEL SULFONYLDIAZOMETHANES, PHOTOACID
GENERATORS, RESIST COMPOSITIONS, AND
PATTERNING PROCESS

INFORMATION DISCLOSURE STATEMENT
(SUBMISSION CONCURRENT WITH THE
FILING OF A NEW PATENT APPLICATION)

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

February 12, 2004

Sir:

Pursuant to 37 C.F.R. §§ 1.97 and 1.98, applicant(s) hereby submit(s) an Information Disclosure Statement for consideration by the Examiner.

I. LIST OF PATENTS, PUBLICATIONS OR OTHER INFORMATION

The patents, publications, or other information submitted for consideration by the Office are listed on PTO-1449, attached hereto.

II. COPIES

- a. ☐ This application was filed before June 30, 2003. Accordingly, submitted herewith is a legible copy of (i) each U.S. and foreign patent; (ii) each publication or that portion which caused it to be listed; and (iii) all other information or that portion which caused it to be listed.
- b. ☒ This application was filed on or after June 30, 2003. Accordingly, copies of cited US patents and patent application publications therefore are not included. Copies of foreign patent documents and non-patent literature are included.

- c. ☐ This application is a National Phase of a PCT application. Some or all of the documents listed on the PTO-1449 are not enclosed because they were cited in the International Search Report and copies should be forwarded from the International Search Authority. If copies are needed, please contact the undersigned.

III. CONCISE EXPLANATION OF THE RELEVANCE
(check at least one box)

- a. ☐ **DOCUMENTS IN THE ENGLISH LANGUAGE**

The patents, publications, or other information listed on the attached PTO 1449 are in the English language and therefore, do not require a statement of relevancy.

- b. ☒ **DOCUMENTS NOT IN THE ENGLISH LANGUAGE**

A concise explanation of the relevance of all patents, publications, or other information listed that is not in the English language is as follows:

English language abstracts are attached to each Japanese patent document.

- c. ☐ **ENGLISH LANGUAGE SEARCH REPORT**

An English language version of the search report or action that indicates the degree of relevance found by the foreign office is attached, thereby satisfying the requirement for a concise explanation. See MPEP 609(III)(A)(3).

- d. ☒ **OTHER**

The following additional information is provided for the Examiner's consideration.

JP-A 3-103854 corresponds to US Patent 5,338,641;
JP-A 8-123032 corresponds to US Patents 5,558,971
and 5,558,976; JP-A 11-190904 corresponds to US
Patent 6,136,502.

FEES


This Information Disclosure Statement is being filed concurrently with the filing of a new patent application; therefore, no fee is required.

If the Examiner has any questions concerning this IDS, he/she is requested to contact the undersigned. If it is determined that this IDS has been filed under the wrong rule, the PTO is requested to consider this IDS under the proper rule and charge the appropriate fee to Deposit Account No. 02-2448.

If necessary, the Commissioner is hereby authorized in this, concurrent, and future replies, to charge payment or credit any overpayment to Deposit Account No. 02-2448 for any additional fees required under 37 C.F.R. § 1.16 or under § 1.17; particularly, extension of time fees.

Respectfully submitted,

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GMM/enm
0171-1064P

Attachment(s) : ☒ Form PTO-1449(s)
☒ Documents
☐ Foreign Search Report
☐ Fee
☐ Other: _____

(Rev. 09/30/03)

Form PTO-1449	ATTY. DOCKET NO. 0171-1064P	APPLICATION NO. NEW
INFORMATION DISCLOSURE CITATION IN AN APPLICATION (Use several sheets if necessary)	APPLICANT OHSAWA et al.	
	FILING DATE February 12, 2004	GROUP UNASSIGNED

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	Kind	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	US 2,354,229		1944-07-25	Walter			
	US 6,261,738	B1	2001-07-17	Asakura et al.			
	US 6,004,724	A	1999-12-21	Yamato et al.			
	US 5,338,641	A	1994-08-16	Pawlowski et al.			
	US 5,558,976	A	1996-09-24	Urano et al.			
	US 6,136,502	A	2000-10-24	Satoshi et al.			
	US 5,558,971	A	1996-09-24	Urano et al.			

FOREIGN PATENT DOCUMENTS

	Office	DOCUMENT NUMBER	Kind	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION	
								YES	NO
		3-103854	A	1991-04-30	JAPAN			Abs	
		10-90884	A	1998-04-10	JAPAN			Abs	
		2001-55373	A	2001-02-27	JAPAN			Abs	
		2001-106669	A	2001-04-17	JAPAN			Abs	
		8-123032	A	1996-05-17	JAPAN			Abs	
		11-72921	A	1999-03-16	JAPAN			Abs	
		11-38604	A	1999-02-12	JAPAN			Abs	
		6-266112	A	1994-09-22	JAPAN			Abs	
		4-211258	A	1992-08-03	JAPAN			Abs	
		2000-344836	A	2000-12-12	JAPAN			Abs	
		11-190904	A	1999-07-13	JAPAN			Abs	
		2906999	B2	1999-04-02	JAPAN			Abs	
		9-301948	A	1997-11-25	JAPAN			Abs	
		2000-314956	A	2000-11-14	JAPAN			Abs	
		9-95479	A	1997-04-08	JAPAN			Abs	
		9-230588	A	1997-09-05	JAPAN			Abs	
		9-208554	A	1997-08-12	JAPAN			Abs	

OTHER DOCUMENTS

(Include Name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.) date, page(s), volume-issue number(s), publisher, city and/or country where published.)

PAQUETTE et al., J. Am. Chem. Soc., Vol. 86, pp. 4383-4385, (1964).
WALTER et al., J. Am. Chem. Soc., Vol. 67, pp. 655-657, (1945).
WAGNER et al., Synthetic Organic Chemistry, pp. 778-781, (1965).
ARIMITSU et al., J. Photopolymer Science & Tech., Vol. 9, No. 1, pp. 29-30, (1996).
ARIMITSU et al., J. Photopolymer Science & Tech., Vol. 8, No. 1, pp. 43-44, (1995).
KUDO et al., J. Photopolymer Science & Tech., Vol. 8, No. 1, pp. 45-46, (1995).

EXAMINER	DATE CONSIDERED
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

GMM